

“Exploring the limits of single-expose EUV patterning at IBM Research”

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Bio:

Nelson Felix has been with IBM since 2008 and is the EUV Technology Lead and Manager of Albany Foundational Patterning Research. His goal is to enable EUV lithography for the IBM and the development alliance for 7 nm and beyond, including scanner and track processes, patterning materials and EUV mask infrastructure. Prior to joining IBM, he received his PhD in Chemical Engineering from Cornell University. He has over 100 publications with over 1000 citations